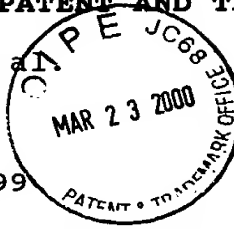


503.37698X00

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): TAKAHASHI, et al.
Serial No.: 09/414,520
Filed: October 8, 1999
For: PLASMA PROCESSING APPARATUS AND A PLASMA
PROCESSING METHOD
Group: 1763



EP 1763 a
Prel. Amtt
#41a
3-2800
Linda B.

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

March 23, 2000

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE CLAIMS

Please amend the claims as follows:

1. (Amended) In a plasma processing apparatus having vacuum processing chamber, a sample table for mounting sample which is processed in said vacuum processing chamber and a plasma generation means, [the plasma processing apparatus], wherein [when] a plasma processing is carried out by generating a plasma [according] in response to [an] introduction of a gas which contains ~~at least~~ carbon and fluorine, and [by generating] a gas species is generated which contains carbon and fluorine according to a plasma dissociation, the plasma processing apparatus comprising:

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